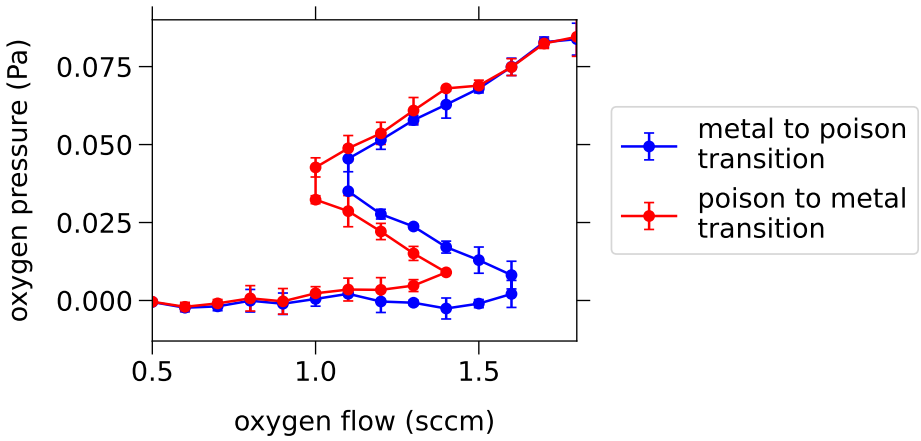

Figure 1: Double hysteresis measured at a constant power of 120 W. Data is taken from reference [2] and is obtained using IV-characteristics. We will present a direct proof of double hysteresis during feedback control instead.

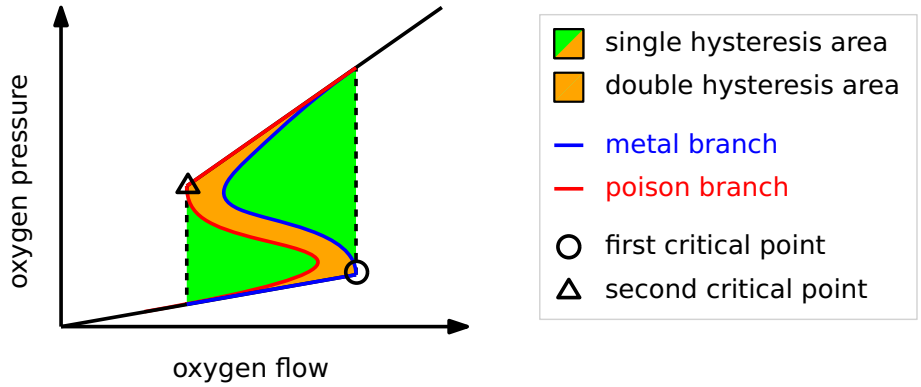

Figure 2: Measures used in the high-throughput analysis to quantify hysteresis behavior. A detailed discussion about the measures is found in reference [4].

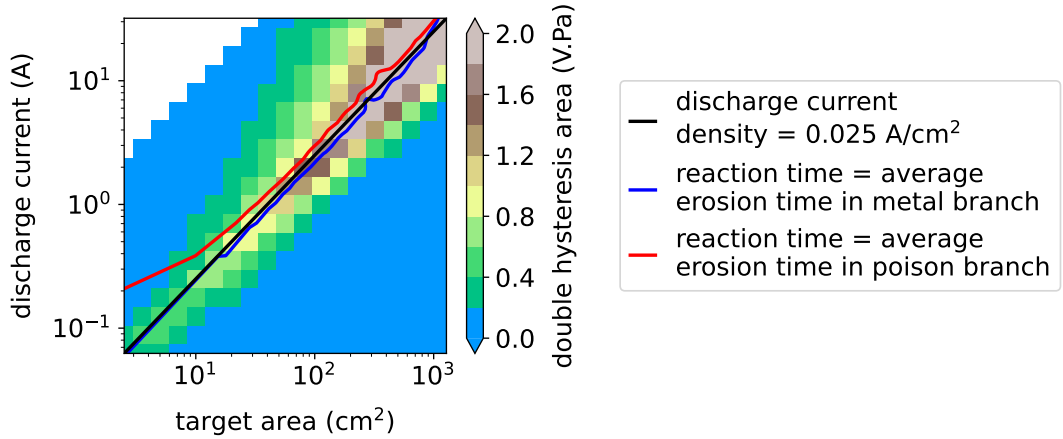

Figure 3: The high-throughput analysis shows that the difference between the two paths in feedback control is maximized at a certain constant discharge current density. This trend can be linked with the relation between the reaction and erosion of implanted oxygen ions. Data is taken from reference [4].

References

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